Amendments to th Claims

A complete list of all the presently or formerly pending claims in the application is provided below, with suitable headings to show the status of each claim and, where appropriate, its current text.

- 1. (Currently Amended) A process for preparing roughened copper surfaces suitable for subsequent multilayer lamination, said process comprising the steps of: (a) applying a highly built alkaline cleaning solution to a copper surface to provide a substantially clean copper surface; and (b) dipping the clean copper surface into an adhesion promoting composition to provide a uniform roughened copper surface suitable for subsequent multilayer lamination, said adhesion promoting composition consisting essentially of an oxidizer, a pH adjuster, a topography modifier, and at least one of a uniformity enhancer and a coating promoter.
- 2. (Currently Amended) The process according to claim 1, said adhesion promoting composition including a coating promoter further consisting essentially of a uniformity enhancer.
- 3. (Original) A process for increasing the adhesion of a dielectric material to a metal surface, wherein the metal surface comprises copper or copper alloys, said process comprising:
 - (a) contacting the metal surface with an adhesion promoting composition comprising an adhesion-promoting effective amount of:
 - (1) an oxidizer;

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- (2) an acid;
- (3) a topography modifier; and
- (4) a coating promoter;
- (b) bonding the dielectric material to the metal surface.
- 4. (Original) A process according to claim 3 wherein the adhesion promoting composition further comprises a uniformity enhancer.
- 5. (Original) A process according to claim 3 wherein the topography modifier is a 5-membered aromatic fused N heterocyclic compound, wherein the N heterocyclic ring has a nitrogen atom at position 1 bonded to a hydrogen atom.
- (Original) A process according to claim 3 wherein the coating promoter is a 5membered aromatic fused N-heterocyclic compound with 1 to 3 nitrogen atoms in the fused ring, wherein none of said nitrogen atoms are bonded to a hydrogen atom.
- 7. (Original) A process according to claim 3 wherein the coating promoter has the following structure:

wherein R1 is selected from the group consisting of hydroxyl groups, amino groups, alkyl groups, hydroxyalkyl groups, aminoalkyl groups, nitroalkyl groups, mercaptoalkyl groups, and alkoxy groups.

8. (Original) A process according to claim 3 wherein the coating promoter is 1-hydroxybeznotriazole.